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(21) International Application Number: PCT/US96/17924 (22) International Filing Date: 8 November 1996 (08.11.96) (30) Priority Data: 08/555,659 13 November 1995 (13.11.95) US (71) Applicant: ALLIEDSIGNAL INC. [US/US]; 101 Columbia Road, P.O. Box 2245, Morristown, NJ 07962-2245 (US). (72) Inventors: KUNKEL, Paul, Frederick; 178 Oehman Boulevard, Cheektowaga, NY 14225 (US). REDMON, Charles, Lewis; 17 Carlton Drive, Orchard Park, NY 14127 (US). SUBBANNA, Somanahalli, Naranappa; 10 Boundbrook Court, East Amherst, NY 14051 (US). (74) Agent: CRISS, Roger, H.; AlliedSignal Inc., Law Dept. (C.A. McNally), 101 Columbia Road, P.O. Box 2245, Morristown, NJ 07962-2245 (US).		(81) Designated States: AL, AU, BB, BG, BR, CA, CN, CU, CZ, EE, GE, IL, IS, JP, KP, KR, LK, LR, LS, LT, LV, MG, MK, MN, MW, MX, NZ, PL, RO, RU, SD, SG, SI, SK, TR, TT, UA, VN, ARIPO patent (KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i>
(54) Title: MANUFACTURE OF VERY LOW ARSENIC HYDROGEN FLUORIDE (57) Abstract The invention provides a process for the preparation of hydrogen fluoride having a very low arsenic level. More specifically, the invention provides a process in which industrial grade anhydrous hydrogen fluoride, or an intermediate product obtained during the hydrogen fluoride manufacturing process, is contacted with an oxidizer in order to oxidize the arsenic impurity to produce anhydrous hydrogen fluoride with a level of arsenic impurity that is at least less than two parts per billion, or aqueous hydrogen fluoride with a correspondingly low level of arsenic.		